

## Tecnical Data - VERTICAL

	KVS 40	KVS 80	KVS 120
Chamber dimensions, mm	Φ 600, h 400	Φ 750, h 800	Φ 1000, h 1200
High vacuum pumping	Turbo or cryo	Turbo or cryo	Turbo or cryo
Cathodes	6 x up to 12" long	6 x up to 22" long	6 x up to 32" long
DC Power Supply (kW)	Up to 5 kW	Up to 10 kW	Up to 10 kW
RF Power Supply (W) 13,56 MHz	Up to 1500 W	Up to 5000 W	Up to 5000 W
Substrate size	Up to 10"	Up to 20"	Up to 34"
Ultimate Pressure	5 x 10 <sup>-7</sup> mbar (10 <sup>-9</sup> range for UHV versions)		
Substrate Heating	Up to 350°C – Optional up to 800 °C		

## Tecnical Data - HORIZONTAL

	KS 500 H	KS 500 H <i>Dual Chamber</i>	KS 800 H0
Chamber dimensions, mm	Φ 500, h 300	2xΦ 500, h 300	Φ 800, h 300
Magnetron Cathodes	4 x up to 6"	4 x up to 6"	4 x up to 10"
DC Power Supply	Up to 2500 W	Up to 2500 W	Up to 5000 W
RF Power Supply	Up to 1500 W	Up to 1500 W	Up to 3000 W
Substrate Heating	Up to 350 °C – option up to 800°C		
Substrate Cooling	Water or LN circulation		
Substrate Etching/Bias	RF/DC up to 600W		
Ultimate Pressure	5 x 10 <sup>-7</sup> mbar (10 <sup>-9</sup> range for UHV models)		
Pumping System	Cryo or turbomolecular		
Option	Sputtering up		

## Tecnical Data - CONFOCAL

KS 500 C

KS 300 C

Chamber dimensions, mm

Φ 600, h 450

Φ 500, h 400

Magnetron Cathodes

4 x up to 4"

4 x 2"

DC Power Supply

Up to 2000 W

Up to 1000 W

RF Power Supply

Up to 1500 W

Up to 600 W

Substrate Size

Up to 6"

Up to 4"

Substrate Heating

Standard 400 °C sC option up to 800 °C

Substrate Etching/Bias

RF/DC up to 600W

Substrate Cooling

Water or LN circulation

Ultimate Pressure

5 x 10<sup>-7</sup> mbar

Pumping System

Turboturbomolecular